

Direct observation of effective atomic diffusion distances in Zr/2Al multilayers due to self-propagating reactions

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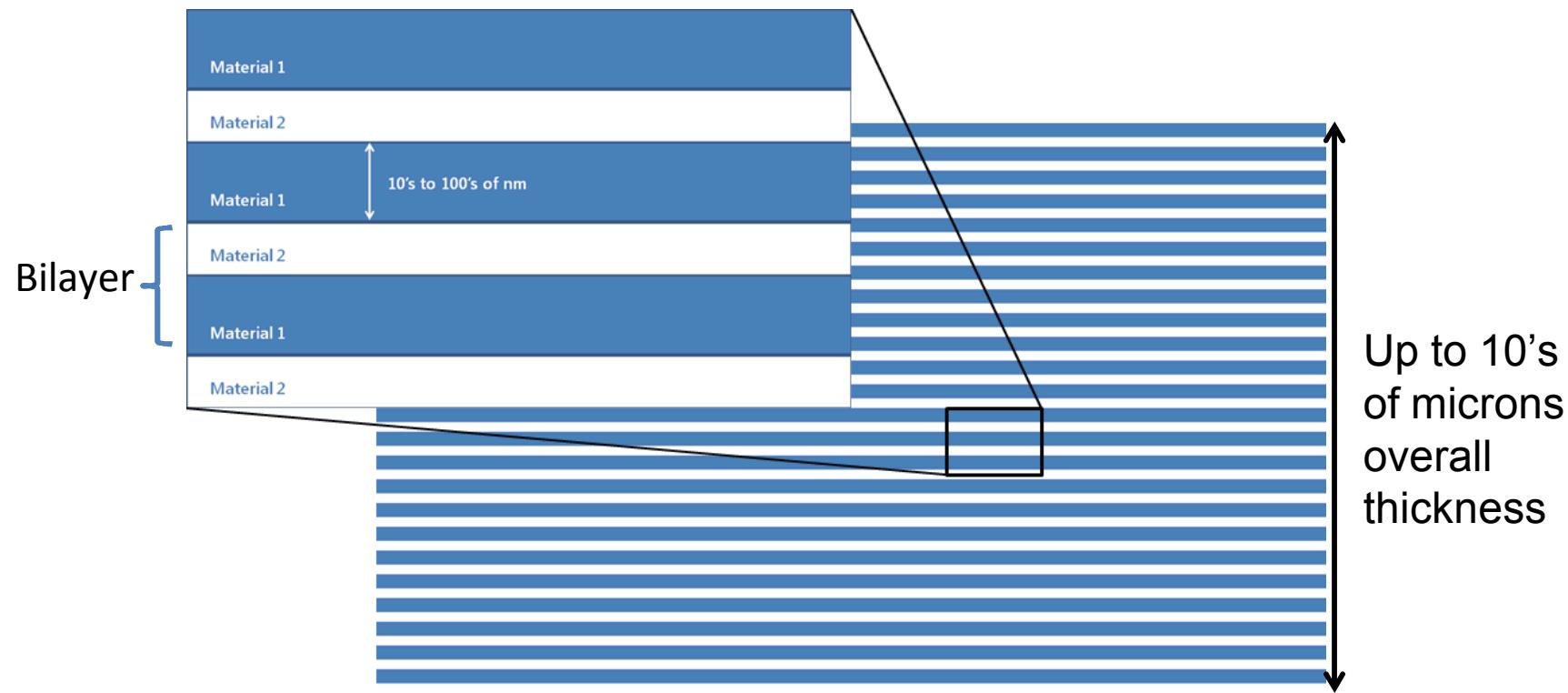
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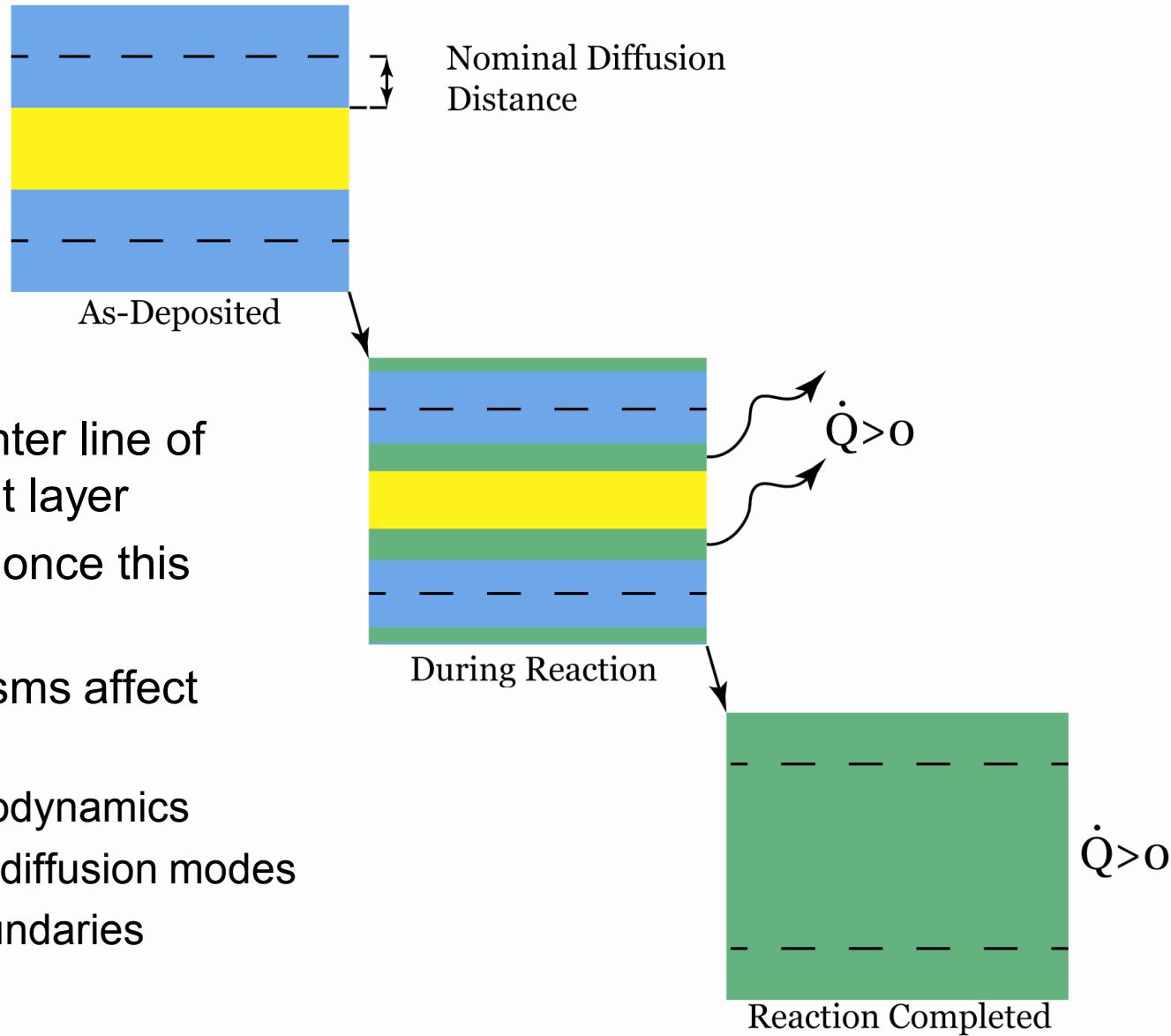
Experimental Material: Zr/2Al

- $Zr + 2Al \rightarrow ZrAl_2$; $\Delta H_{exp} = -46 \text{ kJ/mol atoms}$
(de Boer, Cohesion in Metals)
- Typical design of sputtered reaction foils:
single bilayer per foil, total thickness = 5.0 μm
sputter deposited (pure) metals, full density



Nanolaminates

Assumed Reaction Progression

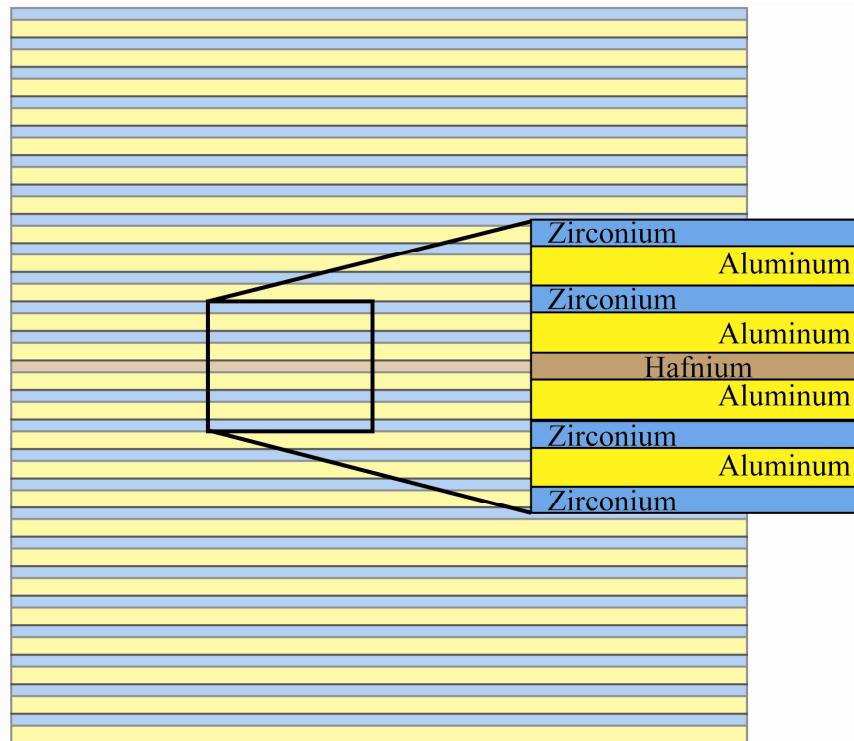


- Atoms diffuse to center line of neighboring reactant layer
- Final phase formed once this distance is traveled
- Can other mechanisms affect diffusion distance?
 - Dissipative thermodynamics
 - High temperature diffusion modes
 - Defects, grain boundaries

Marker Layer Design

Zr/2Al Nanolaminates with one Hf layer

- Hafnium replaces Zr at a single layer
- Hafnium and Zr are miscible with no distinct intermetallic phases
- Similar product phases with Al
- Similar chemistry for Zr and Hf, due to lanthanide contraction

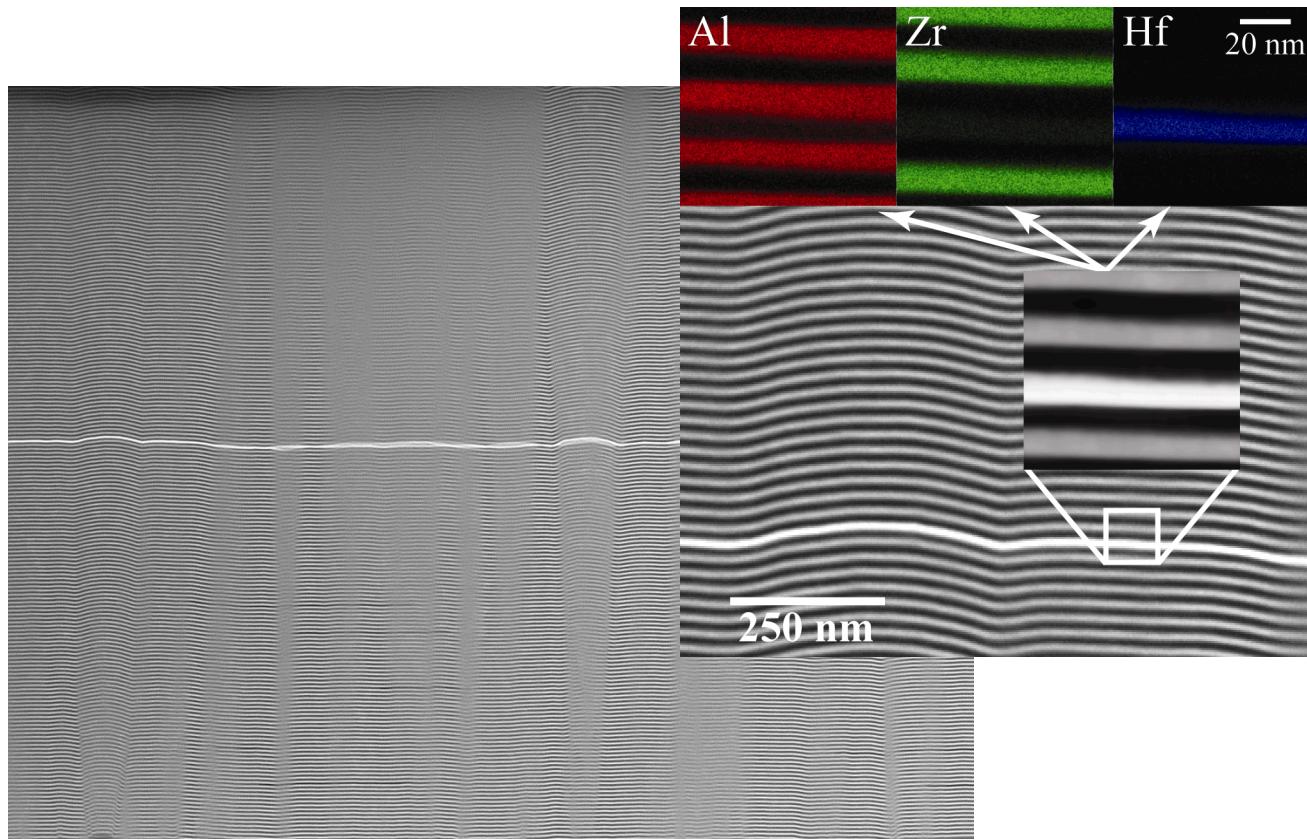


ZrAl ₂	T _m = 1660 °C	HfAl ₂	T _m = 1650 °C
	ΔH = -46 kJ/mol		ΔH = -48 kJ/mol
hP12	a = 0.52824	hP12	a = 0.525
	b = 0.52824		b = 0.525
	c = 0.87482		c = 0.868
Zr ₂ Al ₃	T _m ≈ 1590 °C	Hf ₂ Al ₃	T _m = 1660 °C
	ΔH = -47 kJ/mol		ΔH = -48 kJ/mol
oF40	a = 0.9601	oF40	a = 0.9529
	b = 1.3906		b = 1.3763
	c = 0.5574		c = 0.5525

Marker Layer Design Revealed

Zr/2Al Nanolaminates with one Hf layer

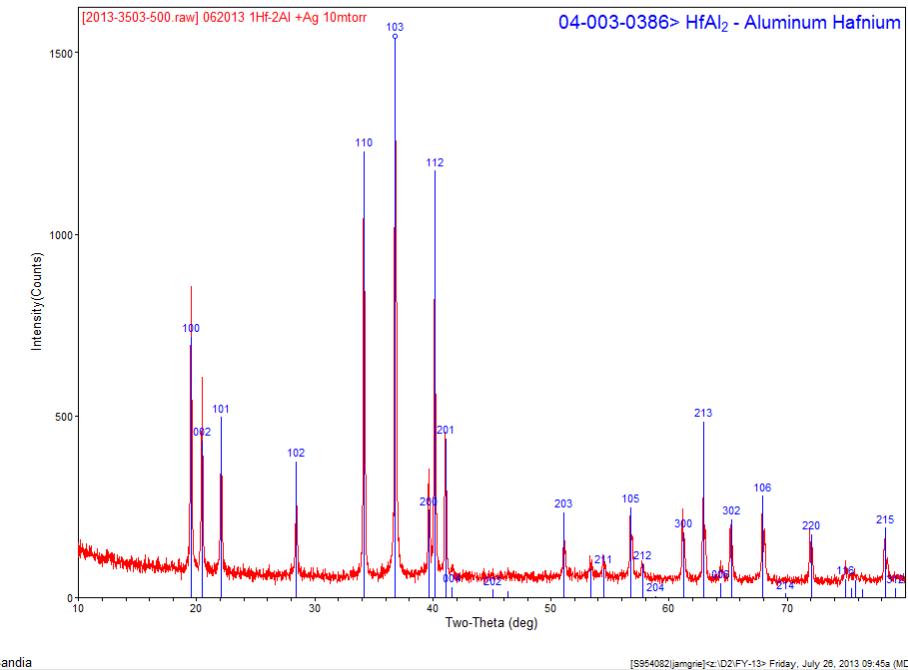
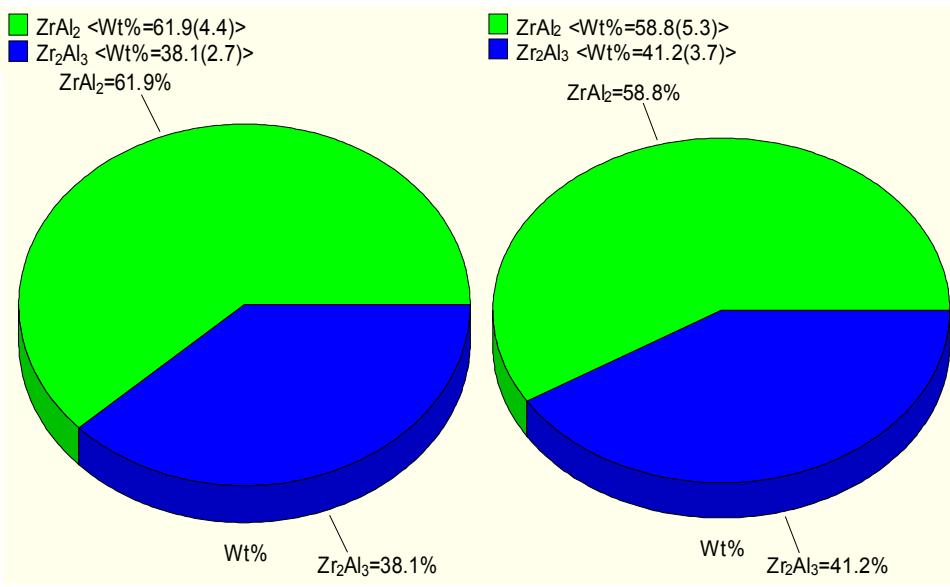
- Marker layer distinct
- Hf placed at center of multilayer
- Clearly resolvable with z-contrast and EDS in TEM



Phase Identification

Zr/2Al and Hf/2Al Standards

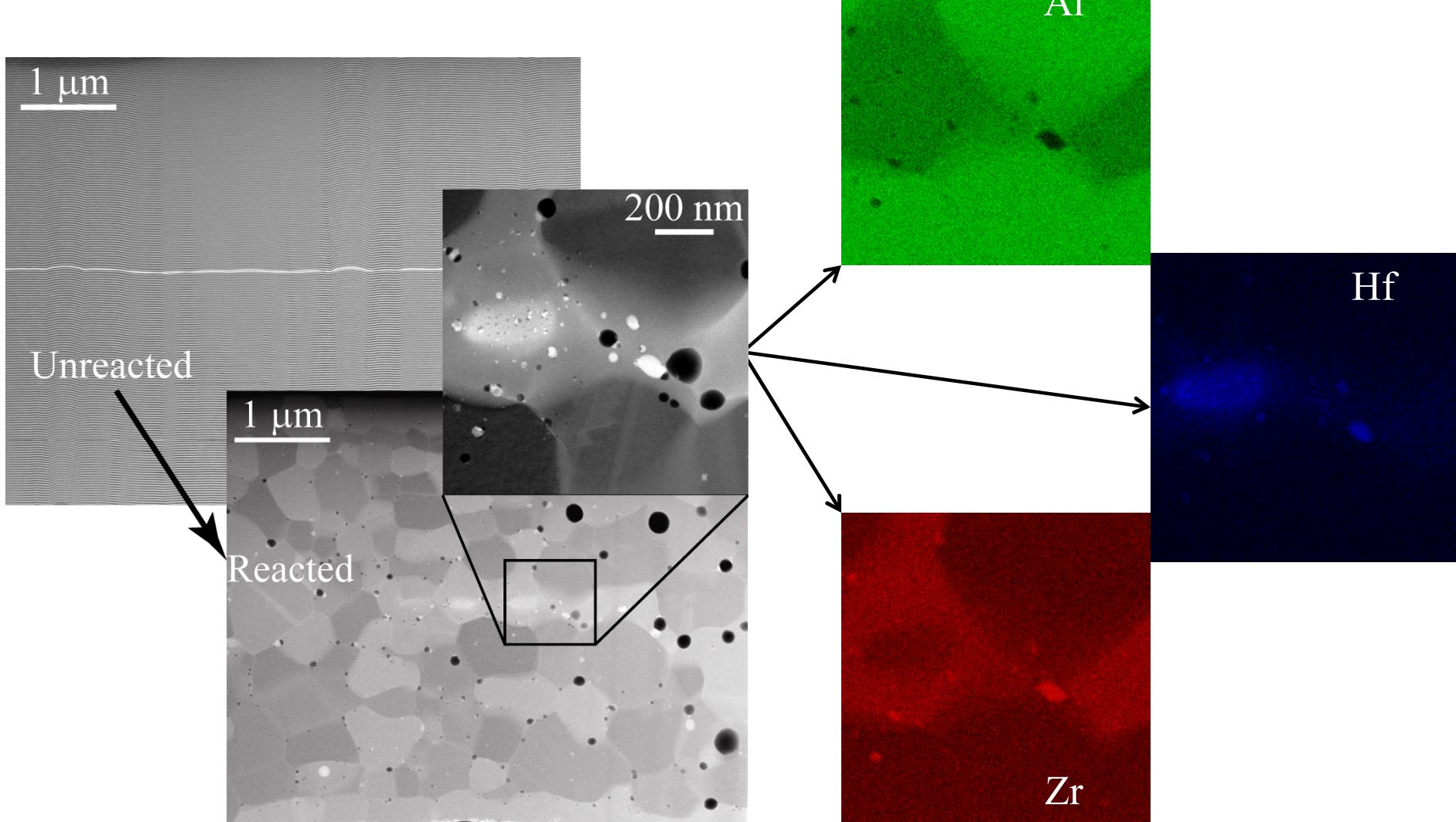
- Zr/2Al films reacted in vacuum (10 mT)
- ZrAl₂ (~60% wt%) & Zr₂Al₃ (~40% wt%) phases identified by XRD
 - Hf/2Al films reacted in vacuum (10mT)
 - Phase pure HfAl₂



Marker Layer Design

Zr+(Hf)/2Al Nanolaminates

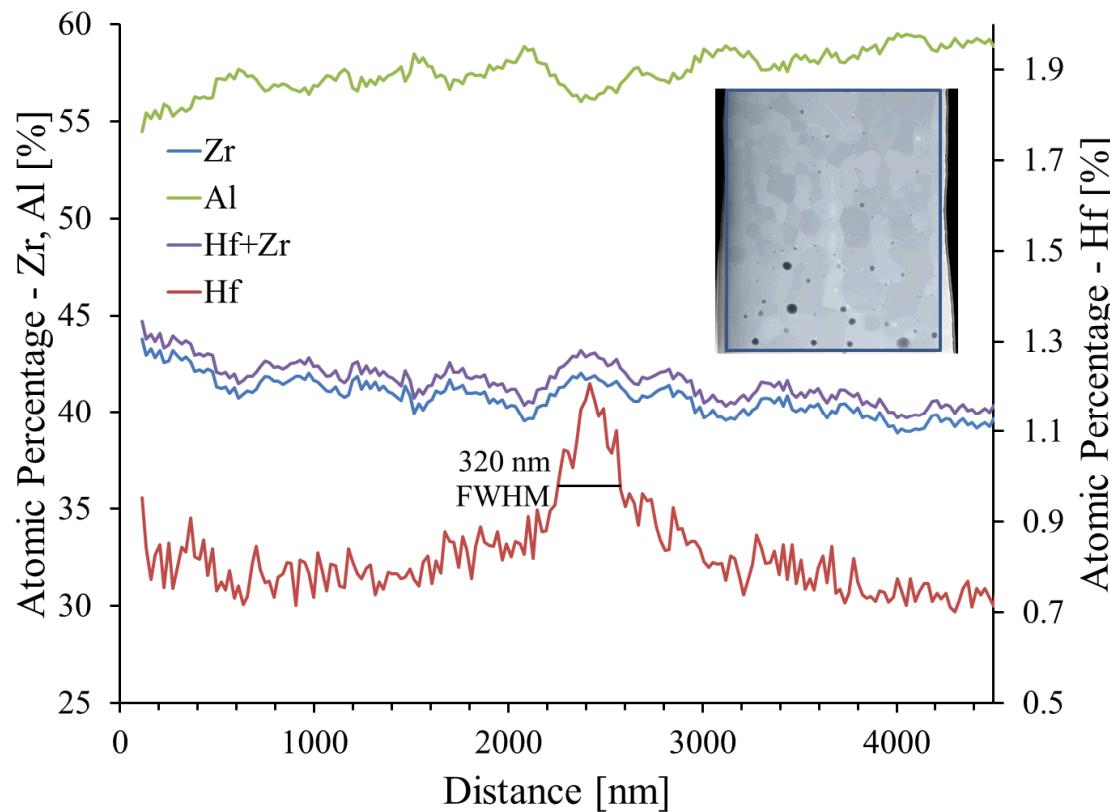
- Reaction disperses Hf marker material



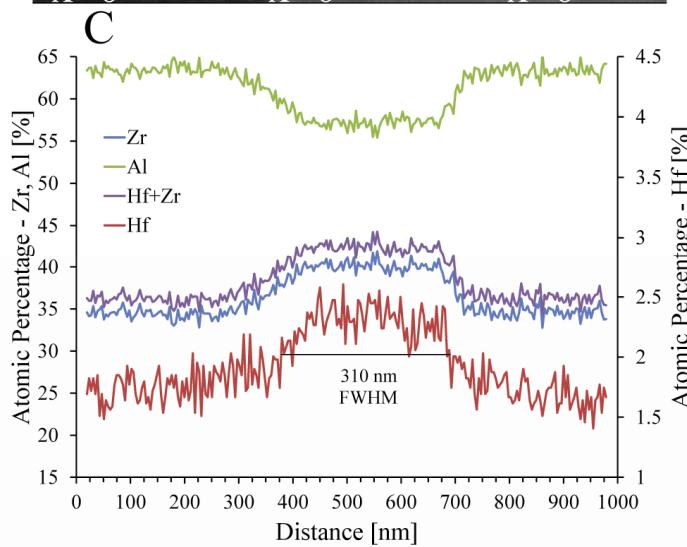
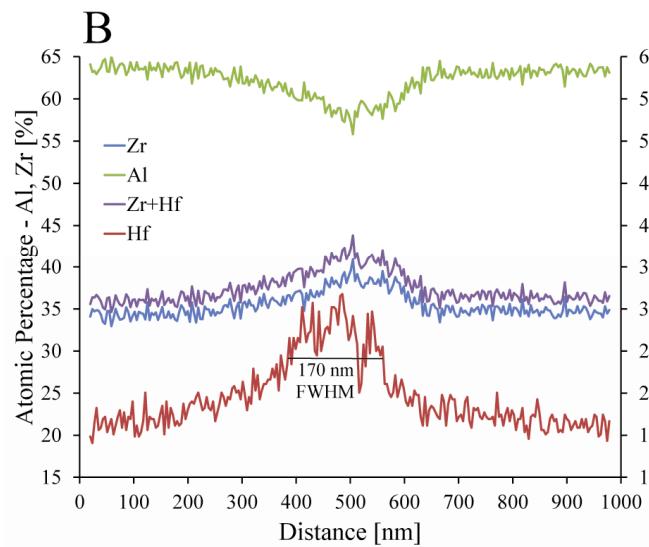
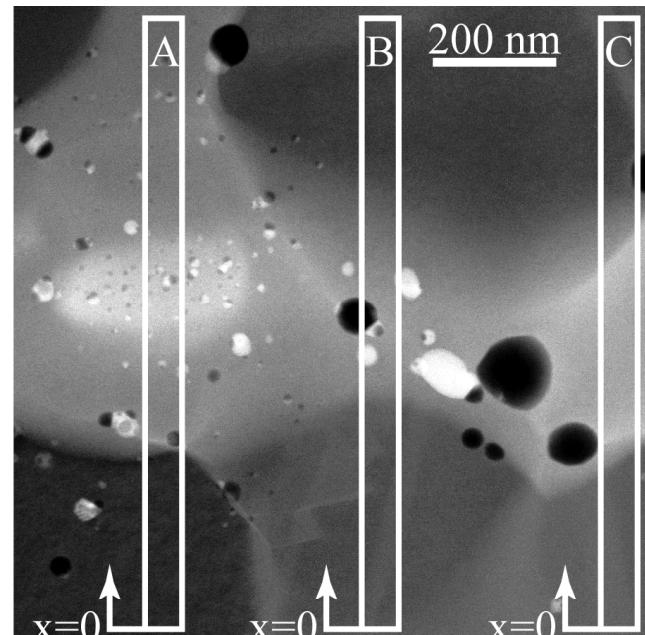
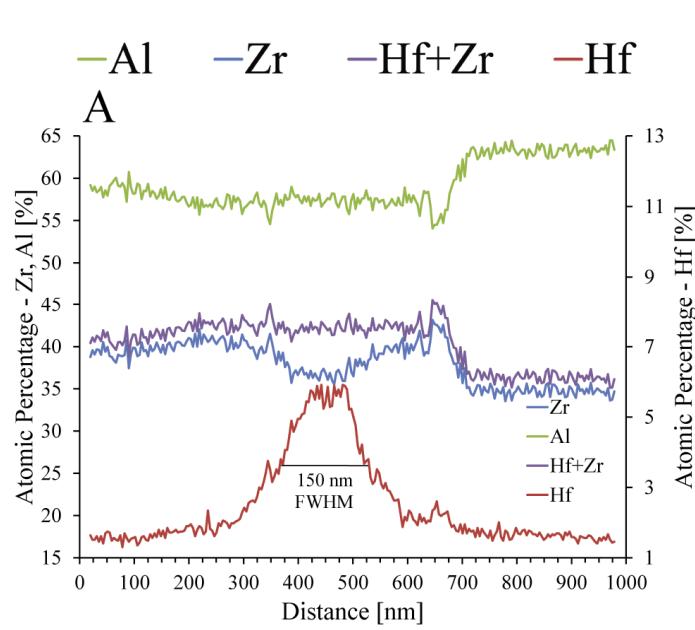
Marker Layer Design

Zr+(Hf)/2Al Nanolaminates

- Reaction disperses Hf marker material
- 14 k \times magnification: 5 \times 5 μm ROI
- Probed through EDS and SIMS



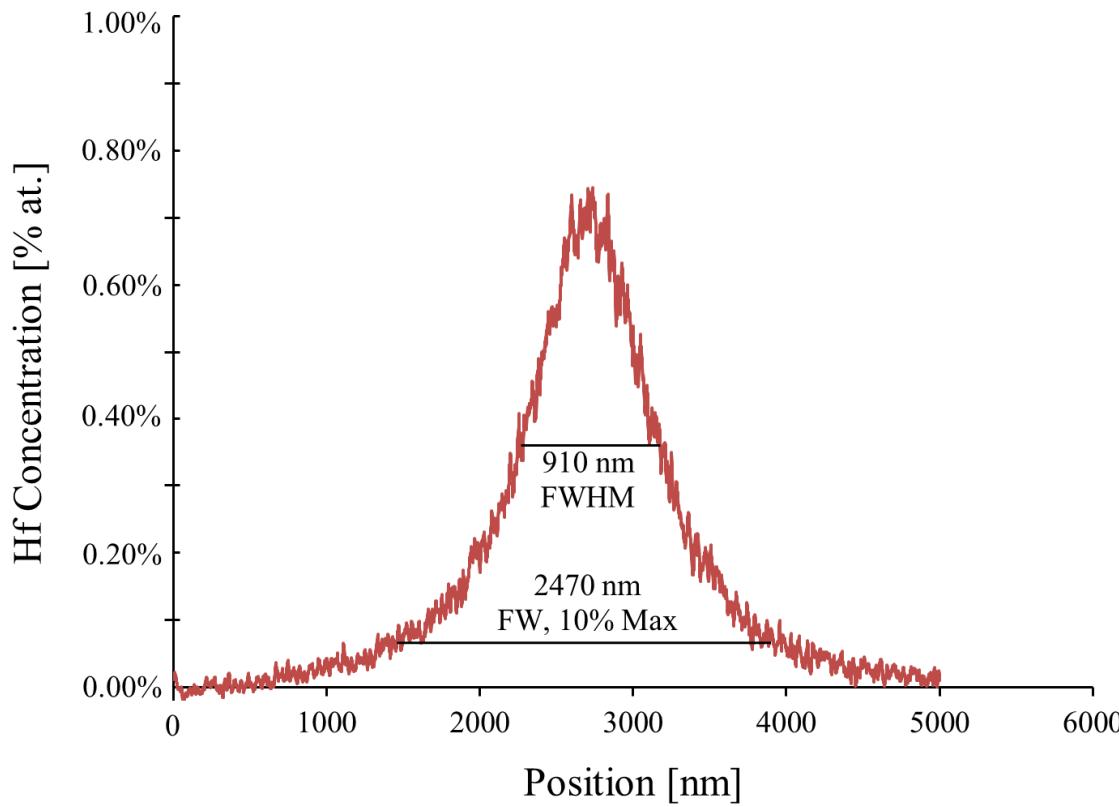
Variation at smaller length scales



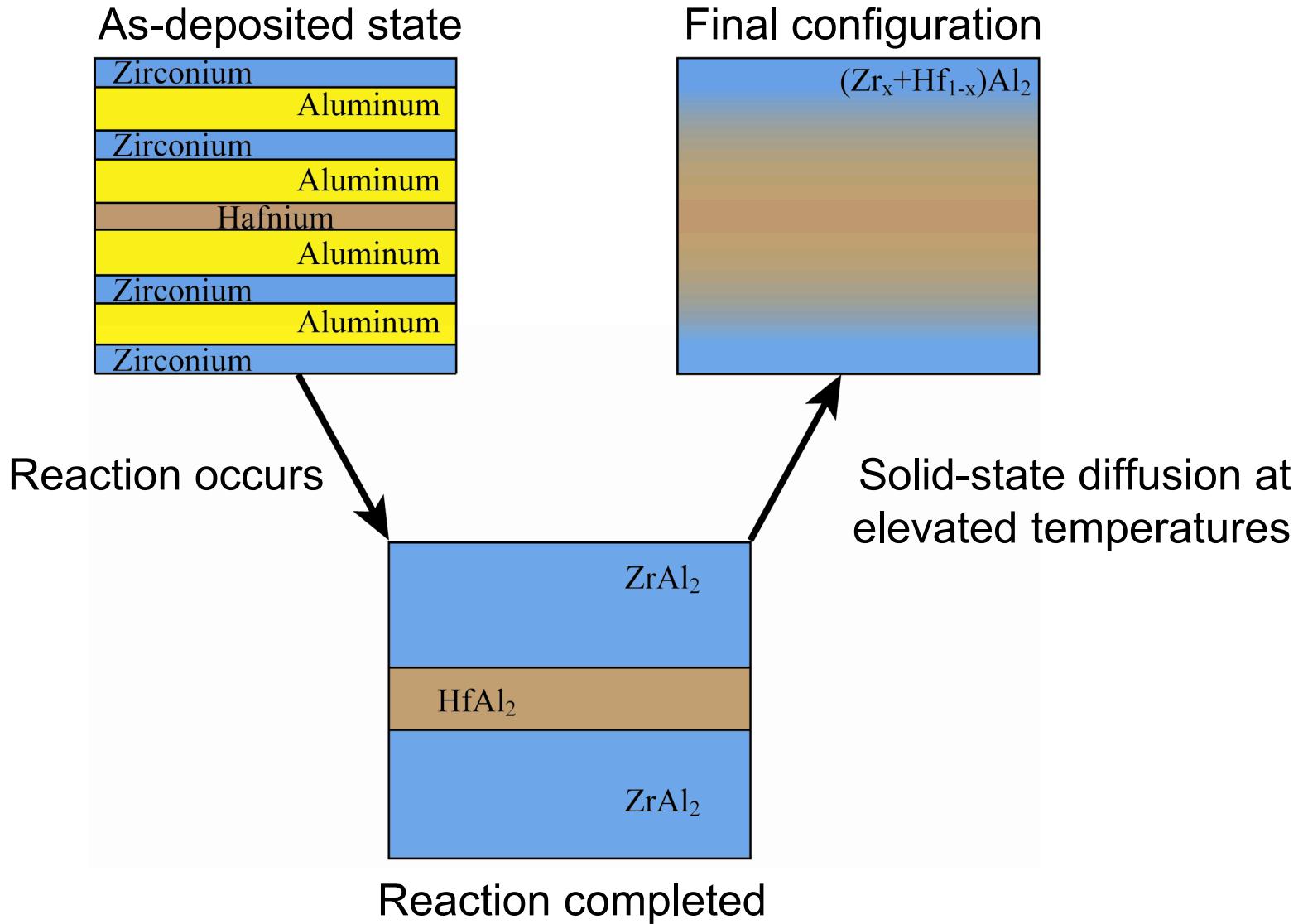
Marker Analysis by SIMS

Zr+(Hf)/2Al Nanolaminates

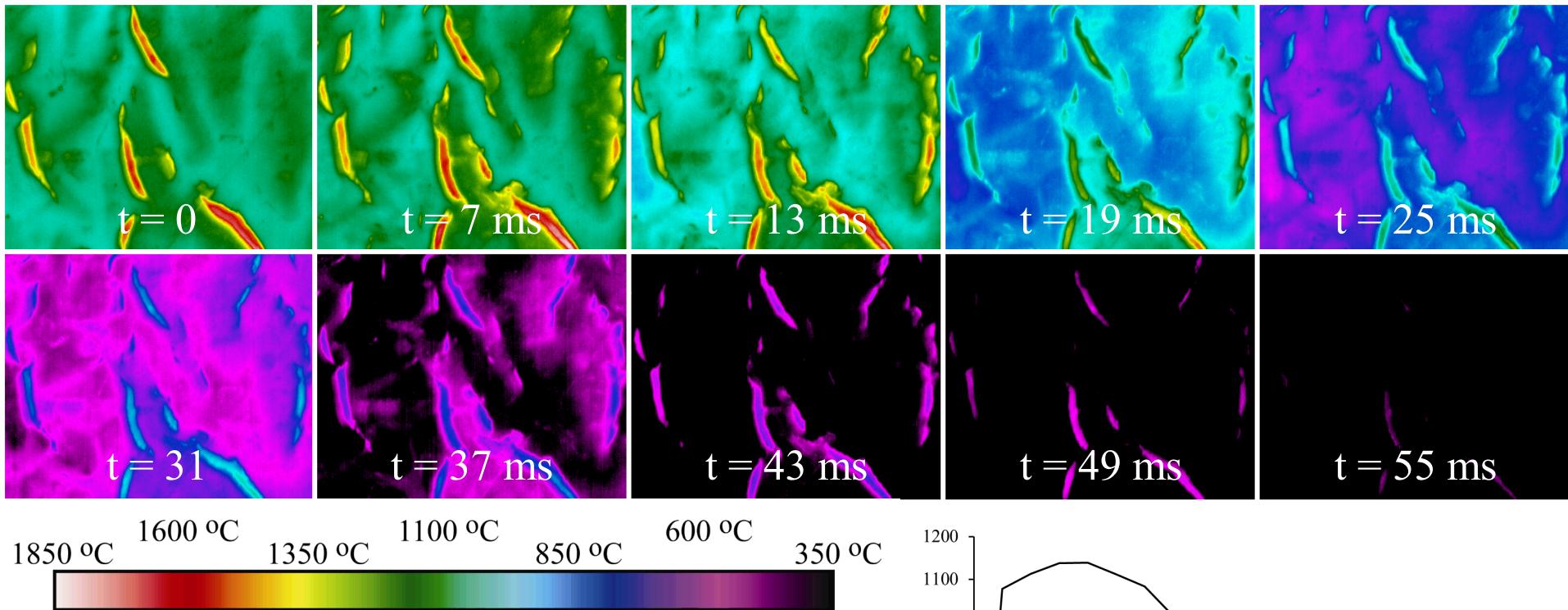
- Sputter area = $200 \times 200 \mu\text{m}^2$
- Analysis area = $50 \times 50 \mu\text{m}^2$ – much greater area than EDS
- Hf-baseline subtracted from signal



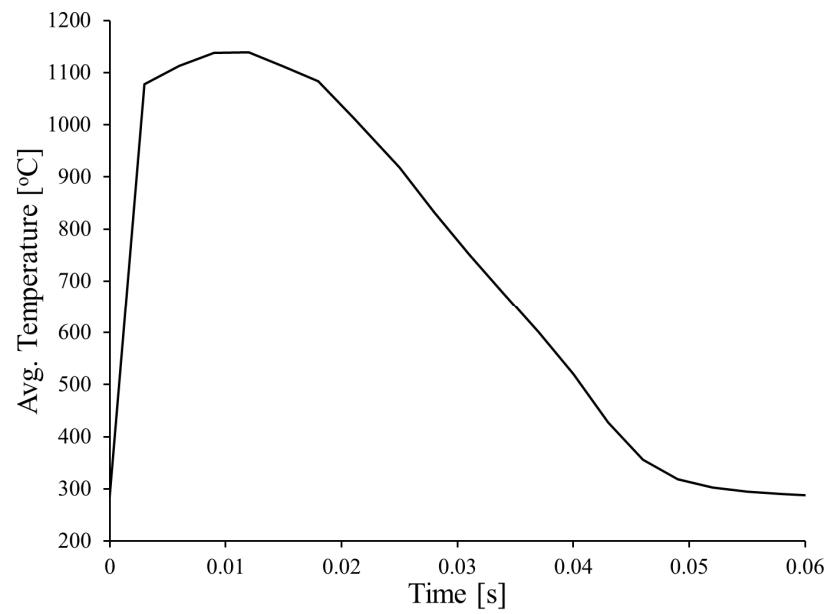
Diffusion model – Assumed progression



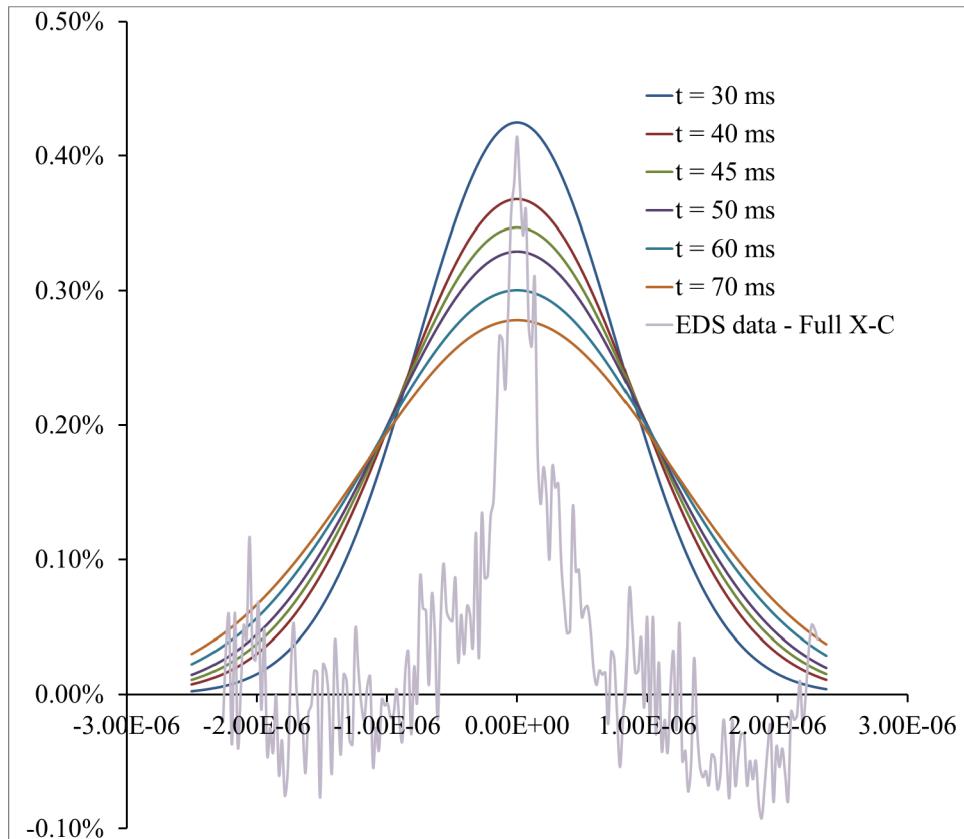
IR imaging of temperature history



- Plot is average meas. temp of surface in image (4.8×3.8 mm)
- Time average over 46 ms is 690°C (963 K)
- Information for comparison to best fit results from diffusion model



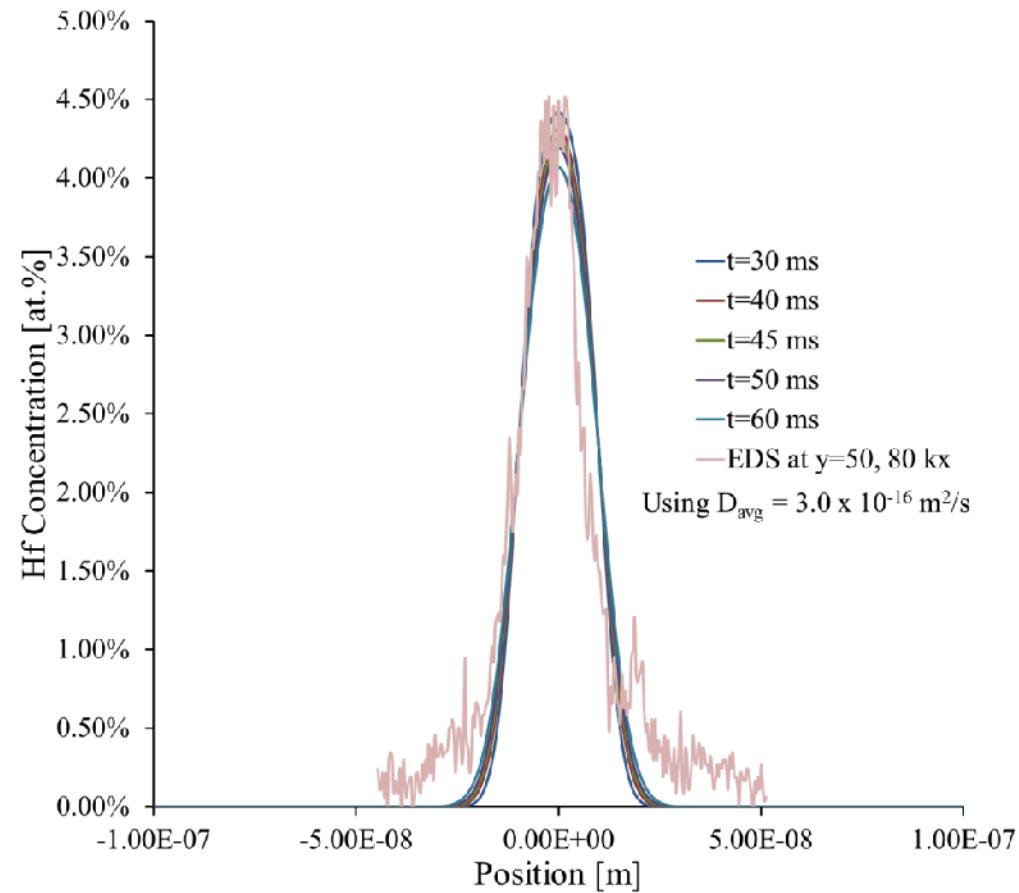
Diffusion model



- Integration of EDS Hf signal over full 14 kx image (5x5 μ m)
- Average D is consistent with solid-state diffusion

50 nmBL

Diffusion model



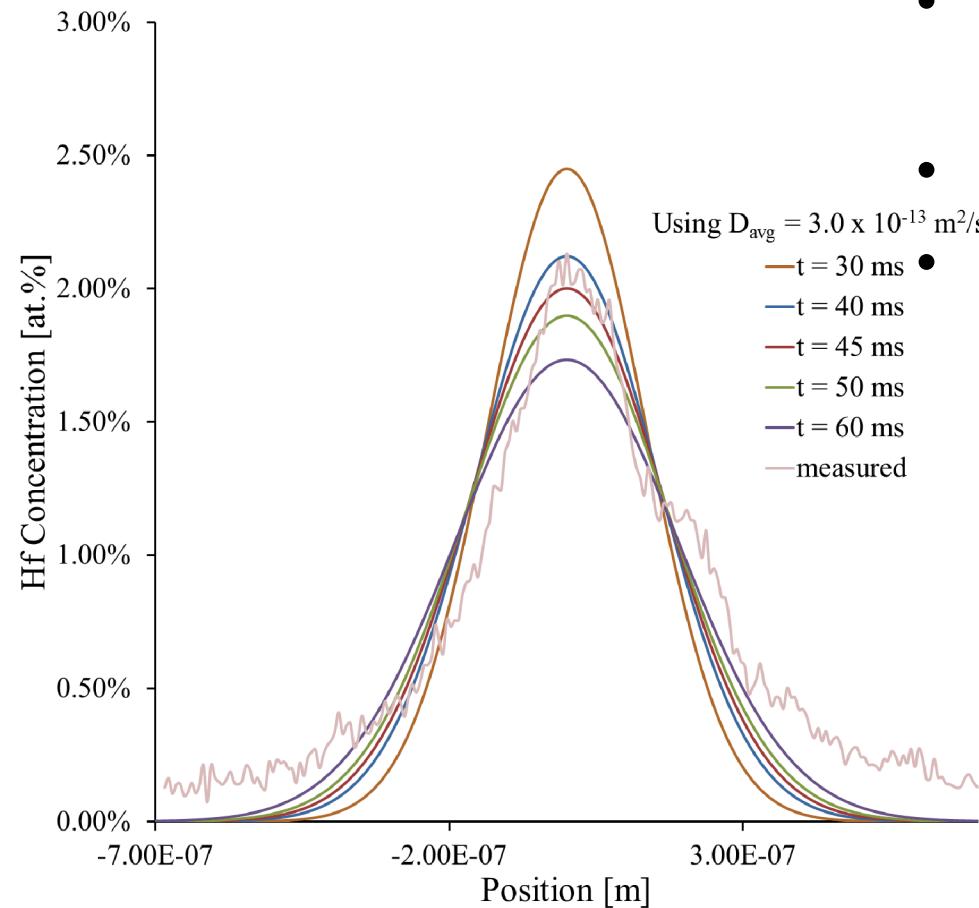
Integrated profile across 40 nm path at location shown,
 $y=50$

80 kx, EDS

Best fit $D = 2.5 \times 10^{-12} \text{ m}^2/\text{s}$

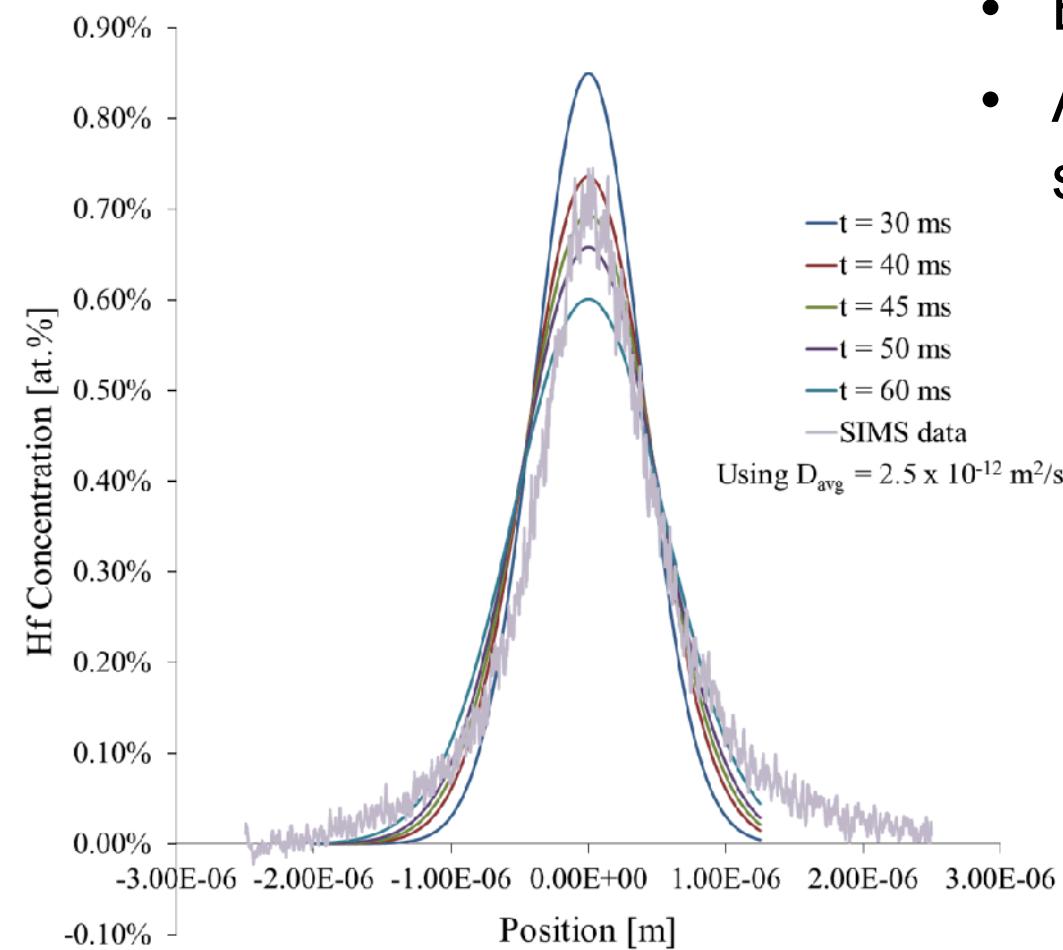
Diffusion model

- Integrated profile across 40 nm path at location shown
- 80 kx, EDS
- **Best fit $D = 2.5 \times 10^{-12} \text{ m}^2/\text{s}$**



Diffusion model – Compare to SIMS data

- Best fit $D = 2.5 \times 10^{-12} \text{ m}^2/\text{s}$
- Average D is consistent with solid-state diffusion, at 960 K



Conclusions

- TEM-EDS and SIMS methodologies allow spatial tracking of marker layer species in reacted multilayers
- Resolution
 - TEM-EDS: spatial: nm, concentration: 0.1%
 - SIMS: concentration: ppm
- Hf marker layers showed atomic diffusion much greater than expected
 - 100's of nm vs. 1's of nm
 - Most likely occurred during elevated temperatures, post-reaction
- Will investigate rapidly quenched materials and unstable fronts